

# AME P5000 Chamber C

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## Facts

The AME P5000 is a multi-chamber tool set up for a variety of processes

- Chamber C - RIE of Silicon Dioxide
  - CHF<sub>3</sub>, CF<sub>4</sub>, and O<sub>2</sub> are used to reactively ion etch silicon dioxide.
- Other Chambers
  - AME P5000 Chamber A - PECVD of TEOS Silicon Dioxide
  - AME P5000 Chamber B - PECVD of Silicon Nitride / Amorphous Silicon

## Personnel

- Tool Engineer - John Nash
- Process Engineer - Sean O'Brien
- Process Engineer - Patricia Meller

## Manuals & Users

- P5000 Manual
- P5000 Certification Checklist